

The Right Strategy for Developing GaN Power Electronics

Burkhard Slischka, Co-founder and CEO, ALLOS Semiconductors 24th October 2017, CPSIC Nanjing



ALLOS is a fabless
IP licensing and technology company

Establish 150 and 200 mm GaN-on-Si technology for all applications on customers' reactors

ALLOS enables customers to master GaN-on-Si epiwafer technology

We are continuously improving our technology to stay ahead

Based on 18 years track record at University Magdeburg,
AZZURRO and ALLOS



ALLOS delivers performance and made-for-manufacturability



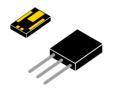
- ✓ 200 mm
- ✓ 725 µm thickness
- 7 μm epi-thickness with0.3 % uniformity
- \checkmark 30 µm bow, no cracks
- √ TDD: 2x10⁸ cm⁻²
- ✓ 0.005 µA/mm lateral leakage @ 600 V
- \checkmark R_{sheet}: 340 Ω /sq.
- \checkmark < 3 USD / cm² total cost

A. Where is GaN-on-Si today?

- B. Who has successfully developed products, and why?
- c. What is the right strategy for fast followers?
- D. Make or buy your GaN-on-Si epiwafers?

The GaN-on-Si revolution is taking place right now

HPE



GaN-on-Si enables more energy-efficient, less complex and smaller high power electronic (HPE) devices out of silicon lines RF





GaN-on-Si provides
higher performance and
lower cost for RF
devices

Micro LED





Only GaN-on-Si allows super-uniform, CMOS-compatible 200 mm epiwafers needed for micro LEDs

How did we get where we are today? And what's next?

Market goes From 'push' to into significant 'pull' market: growth push The system designers start **Products** 2020 to work with (600 V) from GaN-on-Si commercial Rest-of-thepioneers start 2016/2017 world 'wakes Commercial entering the up' and many market traction (HPE): ✓ Yole predicts companies The three Devices: market to start programs GaN-on-Si ✓ Sanken approach pioneers: 2015 ✓ Furukawa 200 m USD in 2020 ✓ Nagoya ✓ IR ✓ Will future market. Institute Epiwafers: shares be divided ✓ Nitronex ✓ AZZURRO 2009 now? ✓ University ✓ How to catch up 2003 Magdeburg fast enough? < 2000

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Yole describes four strategy approaches to GaN-on-Si

Strategy approach

IDM

Device vendor with epi

Foundry with epi

External epi supply







TOWERJOZI Wavetek







Source: Yole Développement 2017

All who have already introduced device products to the market follow one of just two of the strategy approaches

IDM

(device design, epi and processing integrated)



Foundry with epi

(fabless product vendor works with epi and processing foundry)



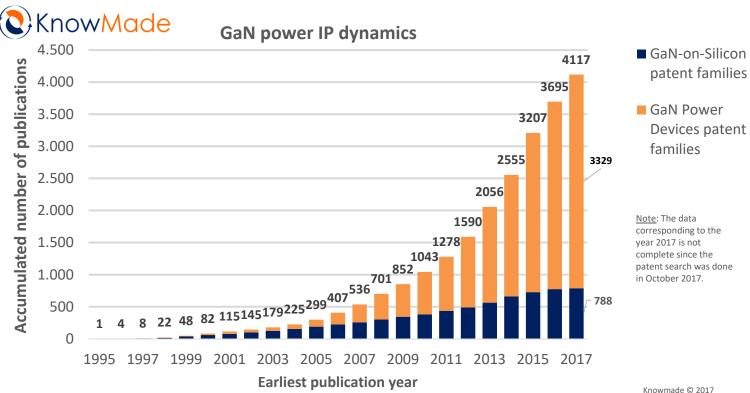


The pattern for successful GaN-on-Si product development



- Started at least five years ago
- Each invested xx to xxx million USD
- Device designers, epi engineers and processing people work closely together
- Epiwafer technology developed in-house
- All work on 150 mm epiwafer diameter
- E-mode HEMT 600 V devices dominate
- Have reference designs and dev. boards

IP space is getting more and more crowded





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Why not wait and see? Why being a fast follower?

- GaN-on-Si is a disruptive technology for the HPE (device maker) industry
- Significant changes in vendor's market shares are possible
- → Fast followers want to benefit from this opportunity

Chairman, ensure the right mind-set for GaN-on-Si



Invest! No business before you built your GaN capabilities



Designs, epiwafer and processing need to be cross-optimized



Seek value on system-level



Epitaxy determines 70 % of performance and value of device



Be prepared for changes and setbacks

Program manager, enable your organization to move fast



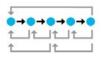
Create an environment where engineers work and learn together



Everyone needs to share a good understanding of designs, epiwafer, processing and their interdependencies



Maximize learning, do many reactor runs and processing cycles



Speed up cycle time, use quick tests, correlate feedback levels



Invest in demonstrators to test and show benefits and reliability

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MAKE epiwafers in-house

Openness

- Open environment, mutual learning
- The team wins and fails together
- Gain better and faster understanding

BUY epiwafers from a vendor

- Two-way confidentiality concerns
- Better material enables your competitor
- Risk for two-way blaming feud

Time-tomarket

- Very fast cycle time
- Very flexible development
- Does built up of epi delay the start?

- Start device development immediately
- Can you avoid being slowed down by cross-organizational coordination?

Cost

- Investment and fixed running cost
- Only marginal cost for each additional wafer
- Who pays customization effort?
- Supplier needs to charge full cost for each additional wafer

Strategy

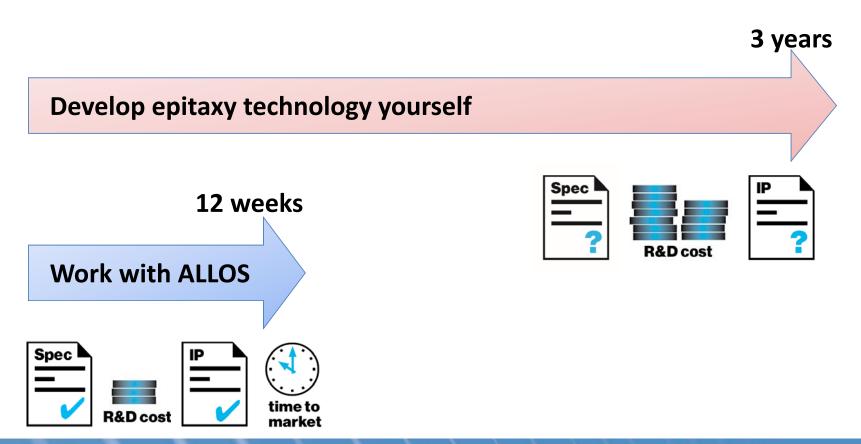
- Full ownership of development result
- Have control over entire value chain
- Being faster and independent

- Focus on fewer things
- Limit your financial exposure

Summarizing: A possible epi strategy for device maker

- → Start device and processing development with purchased epiwafers
- → In parallel set-up in-house GaN-on-Si epi operations
- → Enter production with integrated product (own epi, own processing)
- → Explore option to use large-volume, low-cost, epi-foundry for scaling to mass production in the long run

An offer like ALLOS' makes a fast follower strategy attractive





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